

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention

HIGH PRESSURE PROCESSING CHAMBER FOR
SEMICONDUCTOR SUBSTRATE

Application Number : 09/912844



Confirmation Number: 5915

First Named Applicant: Maximilian Biberger

Attorney Docket Number:

Art Unit:

Examiner:

Search string: (4391511 or 6722642).pn

Certification: This Information Disclosure Statement was submitted under the following conditions, which satisfies the requirement under 37 CFR 1.97(e). The filer certified:

That each item of information contained in the information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of the information disclosure statement.

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
	1	4391511	1983-07-05	Akiyama et al.			
	2	6722642	2004-04-20	Sutton et al.	B1		

Signature

Examiner Name	Date